



Together with new optics, ECLIPSE is evolving to the next stage.

Modularized to meet industrial microscope applications in diverse fields of industry, including semiconductor devices, packaging, FPDs, electronic components, materials, and precision molds.

The ECLIPSE LV Series continues to evolve while offering various stand and illumination units selectable according to the observation method and purpose.

Four types – motorized and manual types plus dedicated reflected illumination and combined reflected/ transmitted illumination types – are available to meet any application.

Illuminators

Expanded lineup

Added a compact LED illuminator to the existing lineup.

With the use of LED, Nikon illuminators are power saving and achieve long life.



Evolved optical performance

Nikon's CFI₆₀ optical system, highly evaluated for its unique concept of high NA combined with long working distance has further evolved to achieve the apex in long working distance, chromatic aberration correction, and light weight.

Easy Operation

Combination with digital camera

Detection of microscope information, including objective lens information, and motorized unit microscope operation are now possible using imaging software, for more efficient observation and image capture.

Observation Methods

Diverse observation / optical contrast methods

Combinations of a full range of accessories expand the observation methods available when using transmitted illumination, allowing adaptability to a greater diversity of samples.

All models enable brightfield, darkfield, differential interference, fluorescence, polarizing, and two-beam interferometry observation, while the LV100ND and LV100NDA also allow transmission-type differential interference, darkfield, polarizing, and phase contrast observation.



LV-N Series

Model features





Manual type



LV150NA



LV100ND



LV100NDA

Dedicated reflected illumination models

Microscope type

Compatible

observation methods

Compatible stages

Integration with Digital Sight cameras for microscopes

 Objective lens information detection** (when used with combination of Intelligent

information detection and control**

(Nosepiece)

Elements

Motorized type

		Brightfield	Darkfield	DIC	Fluorescence	Polarizing	Two-beam Interferometry
LV150/	Episcopic	0	0	0	0	0	0
LV150NA	Episcopic (LED)	0	0	0		Δ	_

* Use an objective lens appropriate to the observation method. ∴ only simple polarizing observation

- LV-S32 3x2 stage (Stroke: 75 x 50 mm with glass plate)
- *Can be fitted with LV-S32SPL ESD plate
- LV-S6 6x6 stage (Stroke: 150 x 150 mm) *Can be fitted with LV-S6WH wafer holder / LV-S6PL ESD plate
- LV-SRP P revolving stage
- P-GS2 G stage 2 (Used with stage adapter LV-SAD)

• LV-S32 3x2 stage (Stroke: 75 x 50 mm with glass plate) *Can be fitted with LV-S32SGH slide glass holder

- LV-S64 6x4 stage (Stroke: 150 x 100 mm with glass plate)
- LV-SRP P revolving stage
- P-GS2 G stage 2 (Used with stage adapter LV-SAD)
- NIU-CSRR2 Ni-U right handle rotatable ceramic stage (Stroke: 78 x 54 mm)
- C-SR2S right handle stage (Stroke: 78 x 54 mm: Used with stage adapter LV-SAD)

Digital Sight 10 or DS-Fi3 or Digital Sight 1000*

Objective lens Nosepiece LV-NU5I and LV-INAD)

Digital Sight 10 or DS-Fi3 or Digital Sight 1000*

 Objective lens information detection** (when used with combination of Intelligent Nosepiece LV-NU5I and LV-INAD)

 Information detection and control of objective lens, light intensity, aperture stop, and observation method (brightfield / darkfield / fluorescence)**

Elements



Combined reflected/transmitted illumination models

		Brightfield	Darkfield	DIC	Fluorescence	Polarizing	Two-beam Interferometry	Phase- contrast
	Episcopic	0	0	0	0	0	0	
LV100ND/ LV100DA-U	Episcopic (LED)	0	0	0	_	Δ	_	_
	Diascopic	0	0	0	_	0	_	0

* Use an objective lens appropriate to the observation method. ∆: only simple polarizing observation

Note: *With imaging software NIS-Elements L and F, functions above are not available. Use NIS-Elements D/Br/Ar. **Excluding Digital Sight 1000

Evolved optical performance

Nikon's CFI60 optical systems are highly evaluated for their unique concept of high NA combined with a long working distance. These lenses have been developed further and evolved achieving the apex in long working distance specifications, correct chromatic aberration, and an optimized lens weight.

T Plan & TU Plan Fluor & TU Plan Apo Lenses

Standard Plan objective lenses

Standard objective lenses

TU Plan Fluor Series

EPI/BD 5x/10x/20x/50x/100x

Enable brightfield, darkfield, simple polarizing, sensitive polarizing, differential interference, and epi-fluorescence observations with just one lens. Achieves superior chromatic aberration performance with long working distance for all magnifications to adapt to any application.



*Brightfield observation (EPI) objective lens

Model	Magnification	NA	Working Distance (mm)
TU Plan Fluor EPI	5×	0.15	23.5
(brightfield type)	10×	0.30	17.5
	20×	0.45	4.5
	50×	0.80	1.0
	100×	0.90	1.0
TU Plan Fluor BD	* 5×	0.15	18.0
(brightfield/darkfield type)	* 10×	0.30	15.0
	* 20×	0.45	4.5
	50×	0.80	1.0
	100×	0.90	1.0

^{*} Uses fly-eye lens.

Low-magnification objective lenses

T Plan EPI

EPI 1x/2.5x

Both clear observation using a conventional analyzer/polarizer and operability-oriented observation without the need of an analyzer/ polarizer are possible.



Model	Magnification	NA	Working Distance (mm)
T Plan EPI	1×	0.03	3.8
(brightfield type)	2.5×	0.075	6.5

Apochromatic objective lenses

EPI/BD 50x/100x/150x

By using phase Fresnel lenses, these objective lenses achieve significantly longer operating distances while maintaining the superior chromatic aberration performance of apochromatic



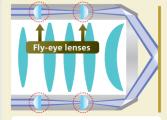
*Brightfield observation (EPI) objective lens

Model	Magnification	NA	Working Distance (mm)
TU Plan Apo EPI	50×	0.8	2.0
(brightfield type)	100×	0.9	2.0
	150×	0.9	1.5
TU Plan Apo BD	50×	0.8	2.0
(brightfield/darkfield type)	100×	0.9	2.0
	150×	0.9	1.5

Dark Field Illumination

Fly-eye lens

Through the use of fly-eye lenses, the CFI60-2 optical system offers bright darkfield illumination throughout the field of view with little unevenness, even for lowmagnification lenses.

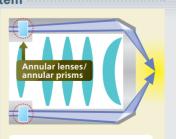


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Fly-eye lenses adjust the diffusion angle of light so light strikes the focal

Darkfield illumination system ·····

As NA and WD improve, objective lenses increase in outside diameter. However, as the width of incident light is fixed, light intensity decreases with conventional illumination systems The illumination system uses annular lenses or annular prisms to increase captured light and achieve bright darkfield illumination with no deterioration



Annular lenses/prisms take in more light to increase brightness

TU Plan ELWD & T Plan SLWD Lenses

Magnification

20x

50x

100×

20×

50×

100×

NA

0.4

0.6

0.8

0.4

0.6

0.8

TU Plan ELWD Series

EPI/BD 20x/50x/100x

Model

TU Plan EPI ELWD

(brightfield type)

TU Plan BD FI WD

(brightfield/darkfield type)

With the phase Fresnel lenses, these objective lenses enable long working distances while offering higher level chromatic aberration correction than conventional objective lenses. This improves operability for samples with different heights.





T Plan IXIO.03 on WO 14	T Plan 2.5x/0.075 ones to u	

Model	Magnification	NA	Working Distance (mm)
Plan EPI	1×	0.03	3.8
brightfield type)	2.5×	0.075	6.5

TU Plan Apo Series

odel	Magnification	NA	Working Distance (mm)
J Plan Apo EPI	50×	0.8	2.0
rightfield type)	100×	0.9	2.0
	150×	0.9	1.5
J Plan Apo BD	50×	0.8	2.0
rightfield/darkfield type)	100×	0.9	2.0
	150	0.0	1 F

Long working distance objective lenses Super-long working distance objective lenses

*Brightfield observation

Working Distance (mm)

19.0

11 0

4.5

19.0

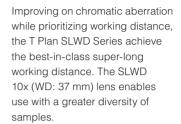
11.0

4.5

(EPI) objective lens

T Plan EPI SLWD







Long working distance / Super-long working distance objective lenses





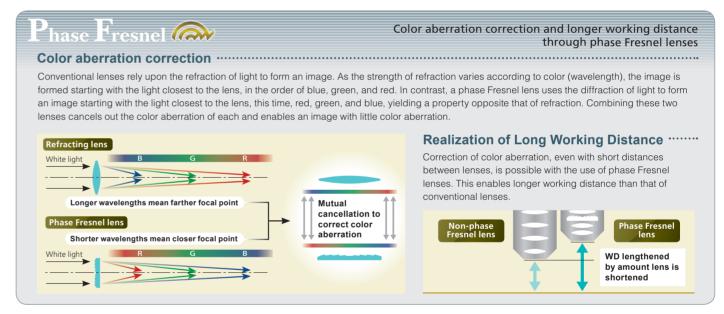








Model	Magnification	NA	Working Distance (mm)
T Plan EPI SLWD	10×	0.2	37.0
(brightfield type)	20×	0.3	30.0
	50×	0.4	22.0
	100×	0.6	10.0



Other lenses

Objective lenses with glass thickness correction features

CFI L Plan EPI CR 20x/50x/100x

Equipped with corrective features that enable high contrast observation of cells or patterns, these observation lenses are unaffected by the glass substrate.



Model	Magnification	NA	Working Distance (mm)
CFI L Plan EPI CR	20× CR	0.45	10.90 - 10.00
(brightfield type)	50× CR	0.70	3.90 - 3.00
	100× CRA	0.85	1.20 - 0.85
	100× CRB	0.85	1.30 - 0.95

Objective lenses for brightfield observation

CFI LE Plan EPI **EPI** 5x/10x/20x/50x/100x







Model	Magnification	NA	Working Distance (mm)
LE Plan EPI	5×	0.1	31.0
(brightfield type)	10×	0.25	13.0
	20×	0.4	3.6
	50×	0.75	0.5
	100×	0.9	0.31

7

Easy Operation

Combination with digital camera

LV150N/LV100ND/LV150NA

Objective lens information detection and control

Information about the objective lens being used can be detected when combining the Intelligent Nosepiece LV-NU5I and the Nosepiece Adaptor LV-INAD. The information is automatically converted to appropriate calibration data when changing the magnification.

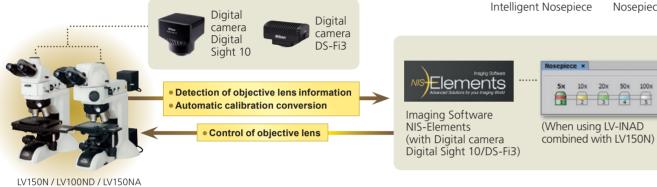
In addition, the LV150NA allows switching of objective lenses via the imaging software.





LV-INAD Nosepiece Adaptor

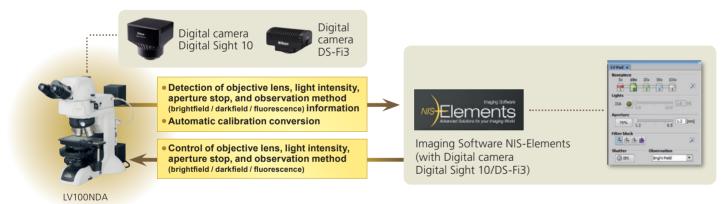
10x 20x 50x 100x



LV100NDA

Microscope information detection and control

The LV100NDA allows detection of information and control of objective lenses, light intensity, aperture stop, and observation method (brightfield / darkfield / fluorescence) via the imaging software, enabling optimization of the conditions vital for image acquisition.



Compatibility Chart of Information Detection and Control by Model						
Information detection and control possible Information detection only	LV150N/LV100ND (When using LV-NU5I and LV-INAD)	LV150NA	LV100NDA (When using LV-UEPI2A Illuminator)			
O. Information detection only	Digital Sight 10/DS-Fi3 (+NIS-Elements)	Digital Sight 10/DS-Fi3 (+NIS-Elements)	Digital Sight 10/DS-Fi3 (+NIS-Elements)			
Objective lens	\circ	©	o			
Reflected illumination *When using (ON/OFF, light intensity adjustment) LV-LH50PC	_	-	0			
Transmitted illumination (ON/OFF, light intensity adjustment)	-	<u> </u>	0			
Aperture stop	_	<u>—</u>	0			
Observation method selector (brightfield / darkfield / fluorescence)		_	0			

Note: With NIS-Elements L and F, functions above are not available. Use NIS-Elements D/Br/Ar.

Camera System

Max Recordable Pixels

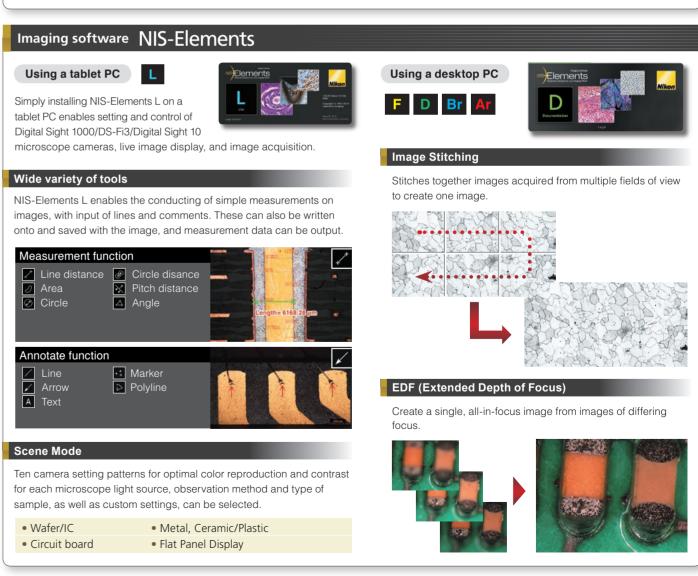
Digital camera system for microscopes "Digital Sight System"

1920×1080

Microscope Camera Digital Sight 10 Digital Sight 1000 DS-Fi3 Equipped with a 2 megapixel CMOS image Three main features of the This high-resolution camera captures both sensor, it can capture full HD microscope previous models, high-resolution, color and monochromatic images at up to images. By connecting a microscope to this high sensitivity and low noise, 6,000 x 3,984 pixels. This enables the wide camera and HDMI monitor, movies and images and high-speed live display are range of images to be captured and then can be captured and saved onto a preoffered in 1 camera. many of them to be stitched together making inserted SD card in the camera. a single and large combined image. Frame Rate 30 fps (1920×1080) 30 fps (1440×1024) 66 fps (1920×1080)

2880×2048

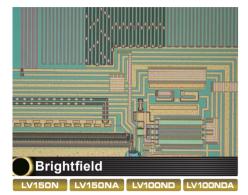
6000×3984



^{*} See the "Digital Camera Digital Sight Series for Microscopes" brochure for details on Digital Sight features.

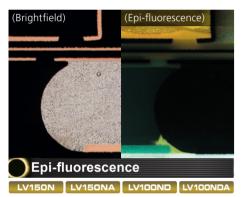
Observation Methods

Compatible with a wide range of observation / optical contrast methods: In reflected light mode -brightfield, darkfield, polarizing, differential interference, epi-fluorescence, and two-beam interferometry, and in Transmitted light mode- brightfield, darkfield, polarizing, differential interference, and phase contrast.



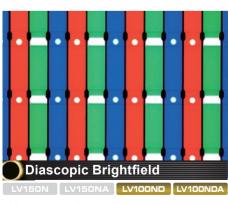
Semiconductors (IC wafers)

From its objective lenses to its illumination systems, the LV-N Series offers thorough measures against flare and provides bright, high-contrast images.



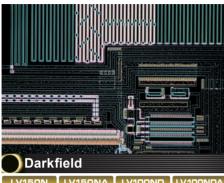
Substrate (solder)

The LV-N Series demonstrates superiority in the observation of samples with fluorescent properties, such as organic ELs or mounted substrates.



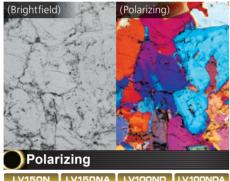
LCD (color filter)

The LV-N Series is effective in the observation of samples with transparency, such as optical components, FPDs, and slide glass samples. When used in conjunction with the C-SP Simple Polarizer and analyzers, transmitted simple polarized observation is possible.



Semiconductors (IC wafers)

The use of Nikon's unique concepts in the objective lens darkfield illumination system enables bright darkfield observation and provides high-sensitivity detection of level differences and defects in samples.



Minerals

The LV-N Series is effective in the observation of samples with birefringent properties, such as liquid crystals or plastics/glass containing distortion.



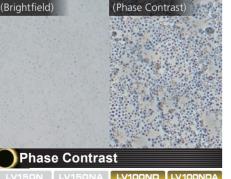
Substrate

Standard-type and high-contrast-type DIC sliders are available to match samples. The LV-N Series is effective for applications such as observation of minute level differences in devices and precision molds.



Mica

Michelson (TI) and Mirau (DI) reflection-type two-beam interferometry is possible with the LV-N Series. When used with micrometer eyepieces, minute level differences can be detected and measured without contact with the sample.



Emulsion

Colorless, transparent samples can be made visible through bright/dark contrast and the use of diffraction and interference, two properties of light.



Nanoparticle (silver)

Colorless, transparent samples can be observed in three dimensions by using polarization to create interference between two beams of light.

Specifications

	LV150N	LV150NA			
Base unit	Maximum sample height: 38 mm (when used with LVNU5A U5A nosepiece and LV-S32 3x2 stage / LV-S64 6x4 stage) *73 mm when used with one column riser 12V50W internal power source for dimmer, coarse and fine adjustment knobs Left: coarse and fine adjustment / Right: fine adjustment, 40 mm stroke Coarse adjustment: 14 mm/turn (with torque adjustment, refocusing mechanism) Fine adjustment: 0.1 mm/turn (1 μm/graduation) Stage mounting hole intervals: 70 x 94 (fixed by 4-M4 screw)				
Nosepieces	Sepieces C-N6 ESD Sextuple Nosepiece ESD LV-NU5 Universal Quintuple Nosepiece ESD LV-NBD5 BD Quintuple Nosepiece ESD LV-NU5I Intelligent Universal Quintuple Nosepiece ESD				
Episcopic Illuminator	LV-UEPI-N LV-LH50PC 12V50W Precentered Lamphouse, LV-LL LED Lamphouse Bright/darkfield switch and linked aperture stop (centerable), field diaphragm (centerable) Accepts ø 25 mm filter (NCB11, ND16, ND4), polarizer/analyzer, λ plate, excitation light balancer; equipped with noise terminator				
	LV-UEPI2 LV-LH50PC 12V50W Precentered Lamphouse, LV-LL LED Lamphouse HG precentered fiber illuminator: C-HGFIE (with light adjustment) *option Bright/darkfield switch and linked aperture stop (centerable), field diaphragm (centerable), automated optical element switching feature matched to brightfield, darkfield, and epi-fluorescence switch Accepts ø 25 mm filter (NCB11, ND16, ND4), polarizer/analyzer, \(\) plate, excitation light balancer; equipped with noise terminator				
Eyepiece tubes	LV-TI3 trinocular eyepiece tube ESD (Erected image, FOV: 22/25) LV-TT2 TT2 tilting trinocular eyepiece tube (Erected image, FOV: 22/25) C-TB binocular tube (Inverted image, FOV: 22) P-TB Binocular Tube (Inverted image, FOV: 22) P-TT2 Trinocular Tube (Inverted image, FOV: 22)				
Stages	LV-S32 3x2 stage (Stroke: 75 x 50 mm with glass plate) ESD compatible LV-S64 6x4 stage (Stroke: 150 x 100 mm with glass plate) ESD compatible LV-S6 6x6 stage (Stroke: 150 x 150 mm) ESD compatible				
Eyepieces	CFI eyepiece series				
Objective lenses	Industrial Microscope CFIso-2/CFIso optical system Objective lens series: Combinations in accordance with the observation method				
ESD performance	1,000 to 10V, within 0.2 sec. (excluding certain accessories)				
Power consumption	1.2 A / 75 W				
Weight	Approx. 8.6 kg Approx. 8.7 kg				

Power consumption	1.2 A / 75 W					
Weight	Approx. 8.6 kg Approx. 8.7 kg					
	LV100ND	LV100NDA				
Base unit	Maximum sample height: 38 mm (when used with LV-NU5 U5 sepiece and LV-S32 3x2 stage / LV-S64 6x4 stage) V50W internal power source for dimmer, coarse and fine adjustment knobs fit: coarse and fine adjustment / Right: fine adjustment, 40 mm stroke arse adjustment: 14 mm/turn (with torque adjustment, refocusing schanism) Fine adjustment: 0.1 mm/turn (1 µm/graduation) Maximum sample height: 33 mm (when used with LVNU5AI Unosepiece and LV-S32 3x2 stage / LV-S64 6x4 stage) 12V50W internal power source for dimmer, coarse and fine adfustment / Right: coarse and fine adjustment / Right: fine adjustment: 14 mm/turn (with torque adjustment, refocusing schanism) Fine adjustment: 0.1 mm/turn (1 µm/graduation)					
Nosepieces	C-N6 ESD Sextuple Nosepiece ESD, LV-NU5 Universal Quintuple Nosepiece ESD LV-NBD5 BD Quintuple Nosepiece ESD, LV-NU5I Intelligent Universal Quintuple Nosepiece ESD D-ND6 Sextuple DIC Nosepiece	LV-NU5AI Motorized Universal Quintuple Nosepiece (High-durability motorized 5-hole universal nosepiece)				
Episcopic Illuminators	LV-UEPI-N LV-LH50PC 12V50W Precentered Lamphouse, LV-LL LED Lamphouse Bright/darkfield switch and linked aperture stop (centerable), field diaphragm (centerable), accepts σ 25 mm filter (NCB11, ND16, ND4), polarizer/analyzer; equipped with noise terminator LV-UEPI2 LV-LH50PC 12V50W Precentered Lamphouse, LV-LL LED Lamphouse HG precentered fiber illuminator: C-HGFIE (with light adjustment) *option Bright/darkfield switch and linked aperture stop (centerable), field diaphragm (centerable), automated optical element switching feature matched to brightfield, darkfield, and epi-fluorescence switch Accepts σ 25 mm filter (NCB11, ND16, ND4), polarizer/analyzer, λ plate, excitation light balancer; equipped with noise terminator	HG precentered fiber illuminator: C-HGFIE (with light adjustment: PC controlled) *option (Motorized operation and control of illumination selector turret (Motorized aperture stop linked to bright/darkfield selector (automatic optimization matched to objective lens), field diaphragm (centerable) (Accepts Ø 25 mm filter (NCB11, ND16, ND4), polarizer/analyzer, λ plate, 16, ND4), polarizer/analyzer, λ plate,				
Diascopic Illuminator	LV-LH50PC 12V50W Precentered Lamphouse (Fly Eye optical system) Internal aperture, field diaphragm, filter (ND8, NCB11); transmitted/reflected selector switch; 12V100W also available (option)					
Eyepiece tubes	LV-TI3 trinocular eyepiece tube ESD (Erected image, FOV: 22/25), LV-TT2 TT2 tilting trinocular eyepiece tube (Erected image, FOV: 22/25), P-TB Binocular Tube (Inverted image, FOV: 22), P-TT2 Trinocular Tube (Inverted image, FOV: 22)					
Stages	LV-S32 3x2 stage (Stroke: 75 x 50 mm with glass plate) / LV-S32SGH slide glass holder LV-S64 6x4 stage (Stroke: 150 x 100 mm with glass plate), LV-SRP P revolving stage / P-GS2 revolving stage: Used with stage adapter LV-SAD NIU-CSRR2 Ni-U right handle rotatable ceramic stage (Stroke: 78 x 54 mm), C-SR2S right handle stage (Stroke: 78 x 54 mm: Used with stage adapter LV-SAD)					
Condensers	LWD achromat condenser (brightfield), LV-CUD U condenser dry (phase contrast, diascopic DIC, darkfield), Achromat 2x-100x slide condenser (brightfield), DF dry condenser (darkfield), and others					
Eyepieces	CFI eyepiece series					
Objective lenses	Industrial Microscope CFI60-2/CFI60 optical system Objective lens series: Combinations in accordance with the observation method					
ESD performance	1,000 to 10V, within 0.2 sec. (excluding certain accessories)					
Power consumption	1.2 A / 75 W 1.2 A / 90 W					
Weight	Approx. 9.5 kg	Approx. 10 kg				

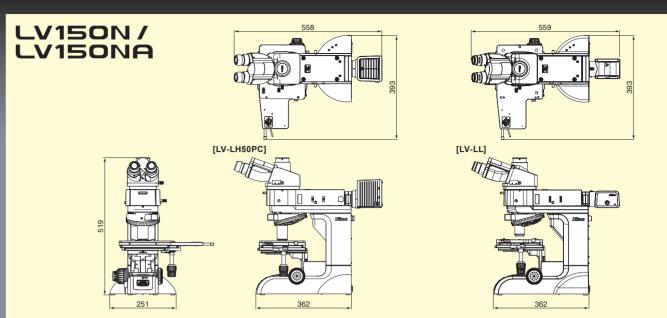
Lens Specifications

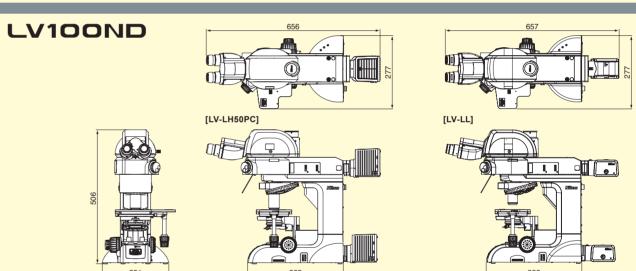
	Туре	Model	Magnification	Product Code No.	NA	Working Distance (mm)
	Турс	T Plan EPI Plan (Semi-apochromat)	1×	MUE12010	0.03	3.8
			2.5×	MUE12030	0.075	6.5
		TU Plan Fluor EPI	5×	MUE12050	0.15	23.5
		Universal Plan Fluor (Semi-apochromat)	10×	MUE12100	0.3	17.5
	Brightfield	o.mo.ou.r.turr.too.(co.m.upos.mo.mu)	20×	MUE12200	0.45	4.5
			50×	MUE12500	0.8	1.0
			100×	MUE12900	0.9	1.0
		TU Plan Apo EPI Universal Plan Apo (Apochromat)	50×	MUC11500	0.8	2.0
			100×	MUC11900	0.9	2.0
			150×	MUC11150	0.9	1.5
		TU Plan Fluor EPI P Polarizing Universal Plan Fluor (Semi-apochromat)	5×	MUE13050	0.15	23.5
	Polarizing		10×	MUE13100	0.3	17.5
			20×	MUE13200	0.45	4.5
			50×	MUE13500	0.8	1.0
			100×	MUE13900	0.9	1.0
	Brightfield Long Working Distance	TU Plan EPI ELWD Long Working Distance Universal Plan (Semi-apochromat)	20×	MUE21200	0.4	19.0
CF160-2			50×	MUE21500	0.6	11.0
			100×	MUE21900	0.8	4.5
	Brightfield Super-long Working Distance	T Plan EPI SLWD Super-long Working Distance Plan (Semi-apochromat)	10×	MUE31100	0.2	37.0
			20×	MUE31200	0.3	30.0
			50×	MUE31500	0.4	22.0
			100×	MUE31900	0.6	10.0
	Brightfield/Darkfield	TU Plan Fluor BD Universal Plan Fluor (Semi-apochromat)	5×	MUE42050	0.15	18.0
			10×	MUE42100	0.3	15.0
			20×	MUE42200	0.45	4.5
			50×	MUE42500	0.8	1.0
			100×	MUE42900	0.9	1.0
		TU Plan Apo BD Universal Plan Apo (Apochromat)	50×	MUC41500	0.8	2.0
			100×	MUC41900	0.9	2.0
			150×	MUC41150	0.9	1.5
	Brightfield/Darkfield Long Working Distance	TU Plan BD ELWD Long Working Distance Universal Plan (Semi-apochromat)	20×	MUE61200	0.4	19.0
			50×	MUE61500	0.6	11.0
			100×	MUE61900	0.8	4.5

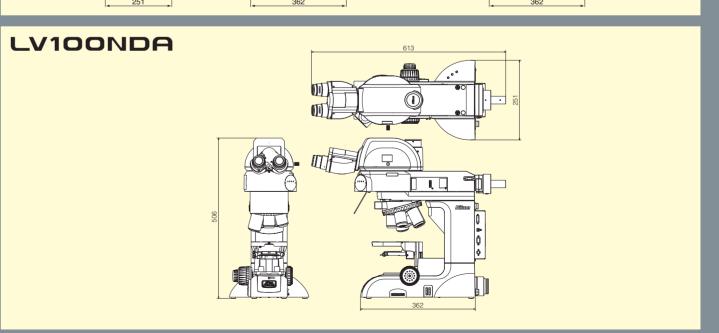
[•] A circular polarizing plate and depolarizer are built into T Plan EPI 1x/2.5x. (Circular polarizing plate can be attached/detached.)

	Туре	Model	Magnification	Product Code No.	NA	Working Distance (mm)
CFI 60	Brightfield With Correction Mechanism	L Plan EPI CR For Inspecting LCDs Plan	20×	MUE35200	0.45	10.9 - 10.0
			50×	MUE35500	0.7	3.9 - 3.0
			100×	MUE35900	0.85	1.2 - 0.85
			100×	MUE35910	0.85	1.3 - 0.95
	Brightfield	L Plan EPI Plan (Achromat)	40×	MUE00400	0.65	1.0
	Brightfield	LU Plan Apo EPI Universal Plan Apo (Apochromat)	100×	MUC00090	0.95	0.4
			150×	MUC10151	0.95	0.3
	Brightfield/Darkfield	LU Plan Apo BD Universal Plan Apo (Apochromat)	100×	MUC40900	0.9	0.51
			150×	MUC50151	0.9	0.42
	Brightfield	LE Plan EPI (Achromat)	5×	MUD00050	0.1	31.0
			10×	MUD00100	0.25	13.0
			20×	MUD00200	0.4	3.6
			50×	MUD00500	0.75	0.5
			100×	MUD00900	0.9	0.31

Dimensions

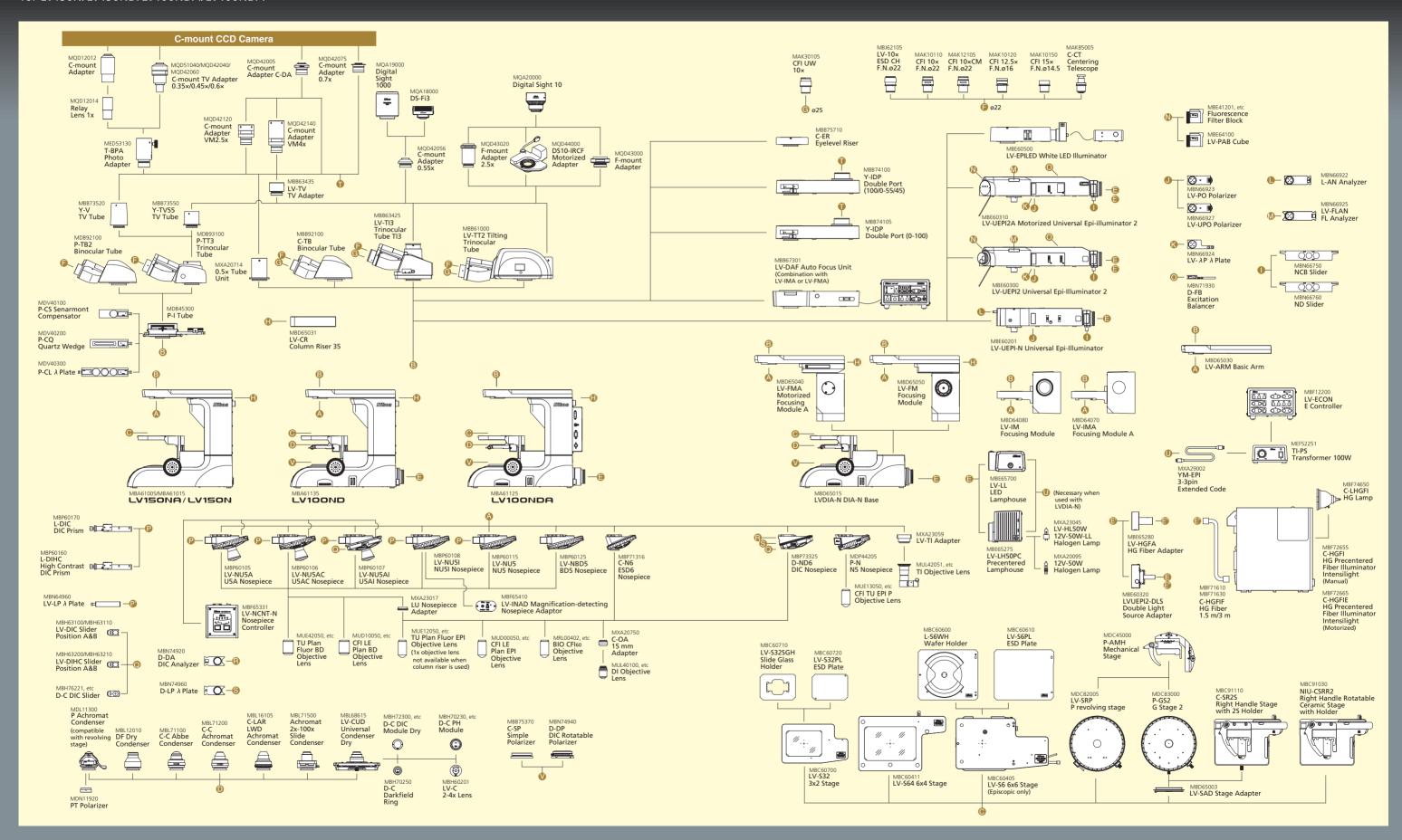






 $2 \hspace{1cm} 1$

for LV150N/LV150ND/LV100NDA/LV100NDA



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Specifications and equipment are subject to change without any notice or obligation on the part of the manufacturer. December 2021 @2012-2021 NIKON CORPORATION

N.B. Export of the products* in this brochure is controlled under the Japanese Foreign Exchange and Foreign Trade Law. Appropriate export procedures shall be required in case of export from Japan. *Products: Hardware and its technical information (including software) Company names and product names appearing in this brochure are their registered trademarks or trademarks.



TO ENSURE CORRECT USAGE, READ THE CORRESPONDING MANUALS CAREFULLY BEFORE USING THE EQUIPMENT.



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